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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
10/796,614	03/08/2004	Chih-Hsing Yu	021653-001000US	1772	
20350	7590 06/23/2005	EXAMINER			
	AND TOWNSEND	LEE, HSIE	LEE, HSIEN MING		
EIGHTH FLO	CADERO CENTER OR	ART UNIT	PAPER NUMBER		
SAN FRANCISCO, CA 94111-3834			2823		
			DATE MAILED: 06/23/2009	5	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application	on No.	Applicant(s)					
Office Action Summary		10/796,61	4	YU, CHIH-HSING					
		Examiner		Art Unit					
		Hsien-min		2823					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply									
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).									
Status									
1)	Responsive to communication(s) filed o	n .							
•		<u> </u>							
• —	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disposition	on of Claims								
4) ☐ Claim(s) 1-20 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) ☐ Claim(s) 11-20 is/are allowed. 6) ☐ Claim(s) is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or election requirement.									
Application	on Papers								
10) 🖾 🛚	The specification is objected to by the Ex The drawing(s) filed on <u>08 March 2004</u> is Applicant may not request that any objection Replacement drawing sheet(s) including the The oath or declaration is objected to by	s/are: a)⊠ accep n to the drawing(s) b correction is require	e held in abeyance. See ed if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CF	FR 1.121(d).				
Priority u	nder 35 U.S.C. § 119								
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 									
2) Notice 3) Inform	c(s) e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO- nation Disclosure Statement(s) (PTO-1449 or PTC r No(s)/Mail Date		4) Interview Summary Paper No(s)/Mail Da		5/21/2005- 0-152)				

DETAILED ACTION

Claim Objections

1. Claim 1 is objected to because of the following informalities: in-consistent term, i.e. "predetermined thickness" (at line 6) versus "first predetermined thickness" (at line 13).

Claim 9 is objected to under 37 CFR 1.75(c), as being of improper dependent form for failing to further limit the subject matter of a previous claim, i.e. the base claim 1 does not recite a step of "forming of silicon nitride." Applicant is required to cancel the claim(s), or amend the claim(s) to place the claim(s) in proper dependent form, or rewrite the claim(s) in independent form.

Allowable Subject Matter

- 2. Claims 11-20 are allowed.
- 3. Claims 2-10 are objected to as being dependent upon an objected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 4. The following is a statement of reasons for the indication of allowable subject matter: The closest prior art of record, Gurba et al. (US 2004/0235203), teaches a related method, comprising: introducing a test wafer 230 into a production run of wafers to form a run of wafers 240 to be processed, each of the wafers being before a gate dielectric production process (i.e. before forming a gate dielectric, Fig. 2E); inserting the run of wafers 240 into a process for gate dielectric production; forming a siliconoxynitride layer 220 to a predetermined thickness 225 (Fig. 2B) of less than 40 Angstroms (paragraph [0035]) at a predetermined temperature using a nitrogen bearing species and an oxygen bearing species (i.e. using NO or N₂O, paragraph [0022])

; and forming a second oxidation (i.e. a rapid thermal anneal, paragraph [0023]) overlying the siliconoxynitride layer 220 to a second thickness.

In contrast, Gurba et al. neither teach nor suggest removing the test wafer from the run; determining a difference value between the first predetermined thickness and the second thickness; and correlating the difference value to one of a plurality of nitrogen concentrations to determine a nitrogen concentration in the first predetermined thickness.

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hsien-ming Lee whose telephone number is 571-272-1863. The examiner can normally be reached on Tuesday-Thursday ($8:00 \sim 6:00$).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available, through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Hsien-ming Lee Primary Examiner Art Unit 2823

June 21, 2005

HSIEN-MING LEE PRIMARY EXAMINEDED DEL/2005